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## **Dr. Larissa Juschkin**

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Larissa Juschkin received her diploma in plasma physics from the Novosibirsk State University, Russia in 1995. In 2001, she received her PhD degree in the field of atomic and plasma physics graduating from the Ruhr University Bochum, Germany. Then, she was employed as the Head of Research & Development by AIXUV GmbH, Germany where she worked on EUV sources and metrology systems until 2005. From 2006 to 2010 she took the lead of the EUV Technology group at the Department of Technology of Optical Systems at the RWTH Aachen University. In 2011, she joined the Plasma Spectroscopy Group at the University College Dublin and worked on the study of short-wavelength radiation from laser-produced plasmas. In 2012, she was appointed to a professorship for Experimental Physics of Extreme Ultraviolet at the RWTH Aachen University. In 2013 she became also the Group Leader of EUV Spectroscopy and Lithography group at the Peter Grünberg Institute 9 Semiconductor Nanoelectronics in Forschungszentrum Jülich in a joint procedure to RWTH professorship. In 2018, she joined KLA Corporation as EUV technologist. Since 2021, she is Program Manager R&D at KLA working on the next generation of wafer inspection tools using broadband plasma radiation. Her scientific focus and research activities combine plasma physics and plasma-based radiation sources with modern nanotechnology applications, especially in the fields of nanostructuring, high-resolution measurement technology and defect detection. She published more than 100 scientific articles and received several patents.